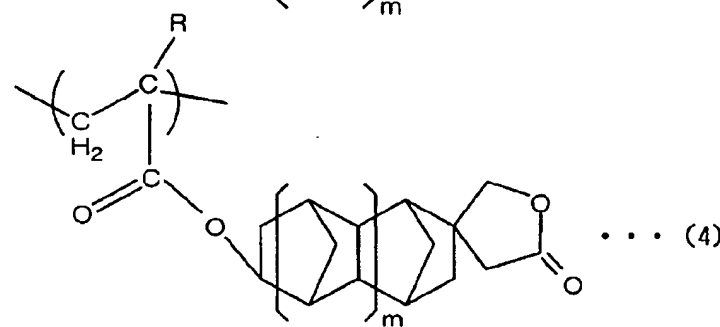
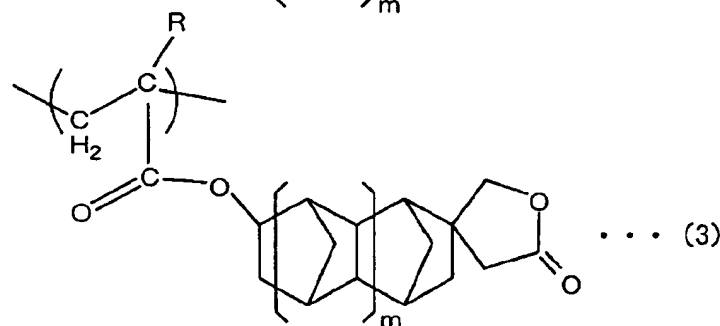
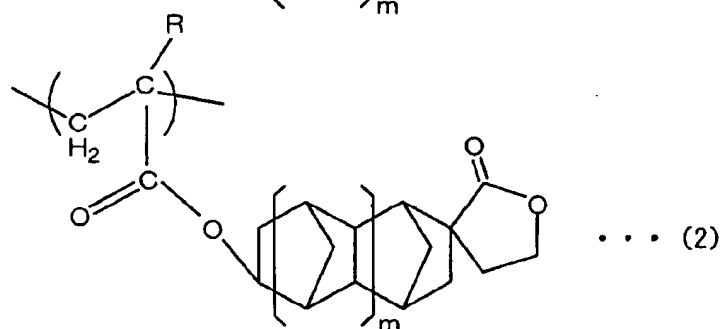
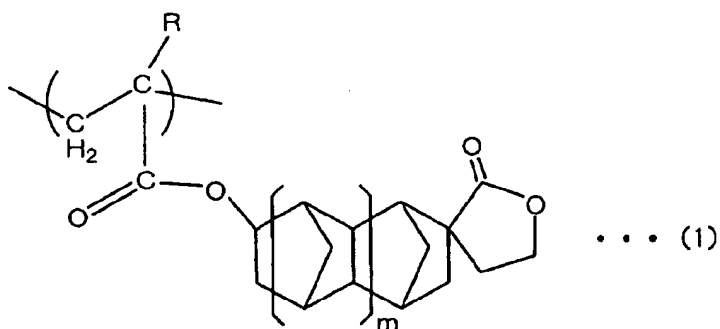


Appl. No. : Unknown
Filed : Herewith

AMENDMENTS TO THE CLAIMS

1. **(Original)** A polymer comprising at least one structural unit (a1) containing a lactone represented by one of general formulas (1) through (4) shown below:



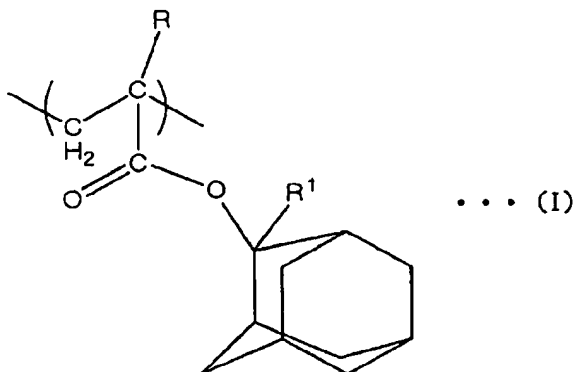
(wherein, in said formulas (1) to (4), R represents a hydrogen atom or a methyl group, and m is either 0 or 1).

Appl. No. : Unknown
Filed : Herewith

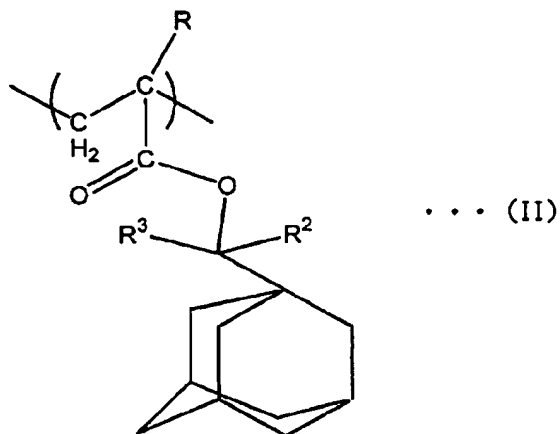
2. **(Original)** A polymer according to claim 1, wherein said structural unit (a1) accounts for 30 to 60 mol% of a combined total of all structural units.

3. **(Original)** A polymer according to claim 1, further comprising a structural unit (a2), which contains an acid dissociable, dissolution inhibiting group, and is derived from a (meth)acrylate ester.

4. **(Original)** A polymer according to claim 3, wherein said structural unit (a2) is at least one unit selected from a group consisting of general formulas (I), (II), and (III) shown below:

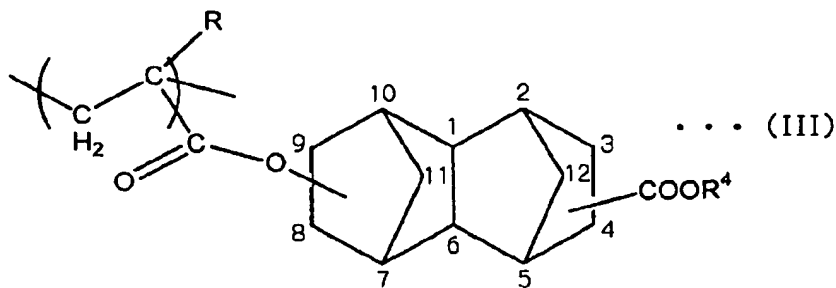


(wherein, R represents a hydrogen atom or a methyl group, and R¹ represents a lower alkyl group)



(wherein, R represents a hydrogen atom or a methyl group, and R² and R³ each represent, independently, a lower alkyl group)

Appl. No. : Unknown
 Filed : Herewith



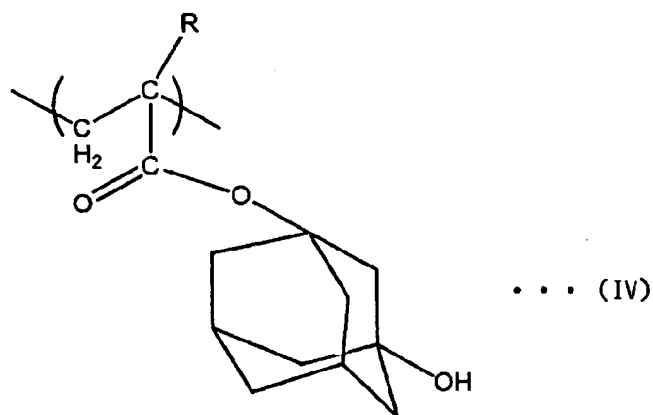
(wherein,

R represents a hydrogen atom or a methyl group, and R⁴ represents a tertiary alkyl group).

5. **(Original)** A polymer according to claim 3, wherein said structural unit (a2) accounts for 20 to 60 mol% of a combined total of all structural units.

6. **(Original)** A polymer according to claim 1, further comprising a structural unit (a3), which contains a hydroxyl group and is derived from a (meth)acrylate ester.

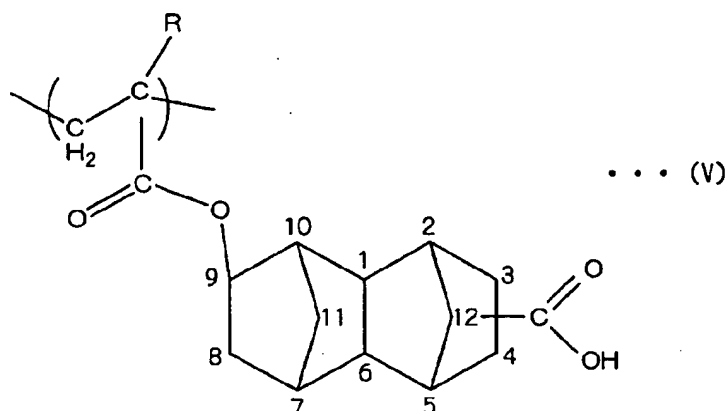
7. **(Original)** A polymer according to claim 6, wherein said structural unit (a3) is one or two units selected from a group consisting of general formulas (IV) and (V) shown below:



(wherein, R

represents a hydrogen atom or a methyl group)

Appl. No. : Unknown
 Filed : Herewith



(wherein, R represents a hydrogen atom or a methyl group).

8. **(Original)** A polymer according to claim 6, wherein said structural unit (a3) accounts for 10 to 50 mol% of a combined total of all structural units.

9. **(Original)** A polymer according to claim 1, wherein said polymer exhibits increased alkali solubility under action of acid, and is used within a positive resist composition.

10. **(Original)** A positive resist composition, comprising a resin component (A), an acid generator component (B) that generates acid on exposure, and an organic solvent (C), wherein

said component (A) comprises a polymer according to claim 9.

11. **(Original)** A positive resist composition according to claim 10, wherein said component (B) is an onium salt with a fluorinated alkylsulfonate ion as an anion.

12. **(Original)** A positive resist composition according to claim 10, wherein said component (C) is a mixed solvent of propylene glycol monomethyl ether acetate and a polar solvent.

13. **(Original)** A positive resist composition according to claim 12, wherein said polar solvent is ethyl lactate.

Appl. No. : Unknown
Filed : Herewith

14. **(Original)** A positive resist composition according to claim 10, further comprising an amine (D).

15. **(Currently Amended)** A method for forming a resist pattern, comprising the steps of applying a positive resist composition according to ~~any one of claim 10 through claim 14~~ to a substrate, conducting a prebake, performing selective exposure, conducting PEB (post exposure baking), and performing alkali developing to form a resist pattern.